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| INFORMATION DISCLOSURE CITATION <i>(Use several sheets if necessary)</i> | | Docket Number (Optional) TWI-32410 | | Application Number NEW | |
| | | Applicant(s) Abdurrahman Sezginer et al. | | | |
| | | Filing Date HEREWITH | Group Art Unit Unknown | | |

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| Examiner <i>me</i> | Date Considered <i>3/25/05</i> |
| Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant. | |